

U.S. Department of Commerce, Patent and Trademark Office	Atty Docket No.	Serial No.
	98-0001-1	894518,970 106519186
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant(s)	
	Tom A. Watson et al.	
	Filing Date	Group
	March 6, 2001 8-26-03-1762	2828

## U.S. Patent Documents

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
AK	AA	4,890,294	12/26/89	Nishimae et al.	372	57	
AR	AB	5,009,963	04/23/91	Ohmi et al.	428	472.2	
AC	AC	5,897,847	04/27/99	Jursich et al.	423	219	
AR	AD	6,024,885	02/15/00	Pendharkar et al.	216	22	
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## Foreign Patent Documents

		Document	Date	Country	Class	Subclass	Translation	Yes	No
		AO							
		AP							
		AQ							
		AR							

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AS	
	AT	
	AU	

Examiner *[Signature]*Date Considered *3-3-05*

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U.S. Department of Commerce, Patent and Trademark Office		Atty Docket No.	Serial No.
		M-7697 US	10649186
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		Tom A. Watson et al.	
		Filing Date	Group 2828
		8-26-2003	Unknown

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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
AK	AA	5,047,115	09/10/1991	Charlet et al.	156	643	
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## Translation

		Document	Date	Country	Class	Subclass	Yes	No
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AK	AR	N. Miki et al., "Vapor-Liquid Equilibrium of the Binary System HF-H <sub>2</sub> O Extending to Extremely Anhydrous Hydrogen Fluoride," (March 1990) J. Electrochem. Soc., Vol. 137, No. 3, ©The Electrochemical Society, Inc., pages 787 - 790
AK	AS	N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 - 1869

Examiner H. Rodriguez Date Considered 3-3-05

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<i>AR</i>	AQ	N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 – 1869
<i>AR</i>	AR	Phil Danielson, "Gas Loads From Elastomer Seals," (January 1999) Vacuum & Thinfilm, pages 14 – 15
<i>AR</i>	AS	STELLA CHEMIFA Corporation, "Fluorine Passivation Technology," (1998) 11 pages

Examiner	<i>Armando Rodriguez</i>	Date Considered	<i>3-3-05</i>
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(Use several sheets if necessary)		Tom A. Watson et al.	
		Filing Date	Group 2828
		8-26-2003	Unknown

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	Document	Date	Country	Class	Subclass	Yes	No	
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<i>AR</i>	AQ	N. Maki et al., "Fluorine Passivation of Metal Surface for Self-Cleaning Semiconductor Equipment," (February 1990) IEEE Transactions on Semiconductor Manufacturing, Vol. 3, No. 1, pages 1 - 11						
<i>Al</i>	AR	M. Maeno et al., "Optimization of Fluorine Passivation of Stainless Steel Surfaces," (May 1992) IEEE Transactions on Semiconductor Manufacturing, Vol. 5, No. 2 pages 107 - 113						
<i>Al</i>	AS	Hashimoto Chemical Corporation, "Fluorine Passivation Technology," (1997) pages 1 - 11						

Examiner <i>Aramis Rodriguez</i>	Date Considered <i>3-3-05</i>
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U.S. Department of Commerce, Patent and Trademark Office		Atty Docket No.	Serial No.
		M-7697 US	10649166
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		Applicant(s)	
		Tom A. Watson et al.	
		Filing Date	Group 2826
		S-26-03	Unknown

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<i>AK</i>	AQ	M. Maeno et al., "Fluorine-Passivated Electroless Ni-P Films," (October 1994) J. Electrochem. Soc., Vol. 141, No. 10, ©The Electrochemical Society, Inc., pages 2649 – 2654
<i>AK</i>	AR	G.M. Jurisch et al., "Gas Contaminant Effects in Discharge-Excited KrF Lasers," (April 20, 1992) Applied Optics, Vol. 31, No. 12, pages 1974 – 1981
<i>AK</i>	AS	W. Holber et al., "Reducing PFC Emissions From CVD Reactors," (March 1999) Vacuum & Thinfilm, pages 26 – 29

Examiner *Humane Rodriguez* Date Considered *3-3-05*

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		8-26-03	Unknown

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<i>AC</i>	AQ	Future Fab International, "XPS Analysis on Fluorine Removal by Plasma Cleaning," (Undated) pages 289 - 293
<i>AC</i>	AR	P.M. Clarke et al., "Gas-Phase Interactions Between WF <sub>6</sub> and Metal Surfaces," (1994) Conference Proceedings ULSI-IX - Materials Research Society, pages 411 - 417; 59 68
<i>AC</i>	AS	Y. Shirai et al., "Fluorine Passivation of Metal Surface," (1996) CleanRooms '96 West Session 602, pages 68 - 71

Examiner *Arnold Rodriguez* Date Considered *3-3-05*

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U.S. Department of Commerce, Patent and Trademark Office				Atty Docket No.	Serial No.		
				M-7697 US	10649176		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				Applicant(s)			
				Tom A. Watson et al.			
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<i>H</i>	AR	Vacuum & Thinfilm, "The Evolution of RF," (November/December 1998) pages 30 - 33					
<i>H</i>	AS	Y. Minamitani et al., "Characteristics of A Corona Reactor As A Gas Purifier For Excimer Lasers," (Undated) pages 1 - 18					
Examiner <i>H. Ray</i>		Date Considered 3-3-05					
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AR	AR	D.W. Greve et al., "Process Control Based On Quadrupole Mass Spectrometry," (1996) J. Vac. Sci. Technol. B14(1), pages 489 - 493
AS	AS	Los Alamos National Laboratory, "Excimer Laser Chemical Problems," (1985) U.S. Dept. of Commerce, 81 pages

Examiner *ATW*

Date Considered

3-3-05

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<i>AK</i>	AP	Kazuhide Ino et al., "Plasma Enhanced <i>In Situ</i> Chamber Cleaning Evaluated by Extracted-Plasma-Parameter Analysis," (1996) IEEE Transaction on Semiconductor Manufacturing, Vol. 9, No. 2, pages 230 - 240
<i>AK</i>	AQ	Kenji Komine et al., "Residuals Caused by The CF <sub>4</sub> Gas Plasma Etching Process," (May 1996) Jpn. J. Appl. Phys. Vol. 35, pages 3010 - 3014
<i>AK</i>	AR	A.L. Cabrera et al., "Surface Analysis Of Copper, Brass, and Steel Foils Exposed to Fluorine Containing Atmospheres," (1990) J. Vac. Sci. Technol. A8, pages 3988 - 3996
<i>AK</i>	AS	I. Kazuhide et al., " <i>In Situ</i> Chamber Cleaning Using Halogenated-Gas Plasmas Evaluated by Plasma-Parameter Extraction," (January 1994) Jpn. J. Appl. Phys. Vol. 33, pages 505 - 509

Examiner *A. P. J.*

Date Considered

3-3-05

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